

# Community consultation about heterogeneous integration

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OCTOBER 25, 2019 | ANDREW FUNG

# Webinar agenda

- (moderator) Andrew Fung, CMC Microsystems Group Lead, Microelectronics and MEMS
- Introduction to CMC Microsystems
- Heterogeneous Integration Roadmap: Integrated Photonics (Prof. Amr Helmy, U. Toronto and member of International Roadmap Committee)
- 2.5D Multi-Technology Silicon Interposer Platform (Gordon Harling, President and CEO, CMC Microsystems)
- Q&A, community feedback

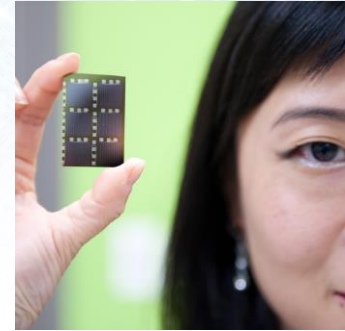
# What is CMC and its role?

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[www.CMC.ca](http://www.CMC.ca)

# CMC Microsystems

- CMC provides services essential for the research and training required to advance Canada's digital economy:
  - Industry 4.0, autonomous vehicles, big data, Internet of Things (IoT), cyber defence and security, 5G, quantum computing, artificial intelligence (AI), and more!



- Academic and Industrial Users
- Not-for-profit founded in 1984
- Manages Canada's National Design Network®
- Delivers micro-nano innovation capabilities across Canada

# Lowering barriers to technology adoption

## CAD



State-of-the-art environments for successful design

- ✓ Selection of high-performance Computer Aided Design (CAD) tools and design environments
- ✓ Available via desktop or through CMC Cloud
- ✓ User guides, application notes, training materials and courses

 [CMC.ca/CAD](https://www.cmc.ca/CAD)

## FAB



Services for making working prototypes

- ✓ Multi-project wafer services with affordable access to foundries worldwide
- ✓ Fabrication and travel assistance to prototype at a university-based lab
- ✓ Value-added packaging and assembly services
- ✓ In-house expertise for first-time-right prototypes

 [CMC.ca/FAB](https://www.cmc.ca/FAB)

## LAB



Device validation to system demonstration

- ✓ Access to platform-based microsystems design and prototyping environments
- ✓ Access to test equipment on loan
- ✓ Access to contract engineering services

 [CMC.ca/LAB](https://www.cmc.ca/LAB)

# Heterogeneous Integration Roadmap: Integrated Photonics

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Prof. Amr Helmy, U. Toronto  
Member of IEEE HIR International Roadmap Committee

- For presentations about the IEEE Heterogeneous Integration Roadmap, visit
- <https://eps.ieee.org/technology/heterogeneous-integration-roadmap.html>

# 2.5D Multi-Technology Silicon Interposer Platform

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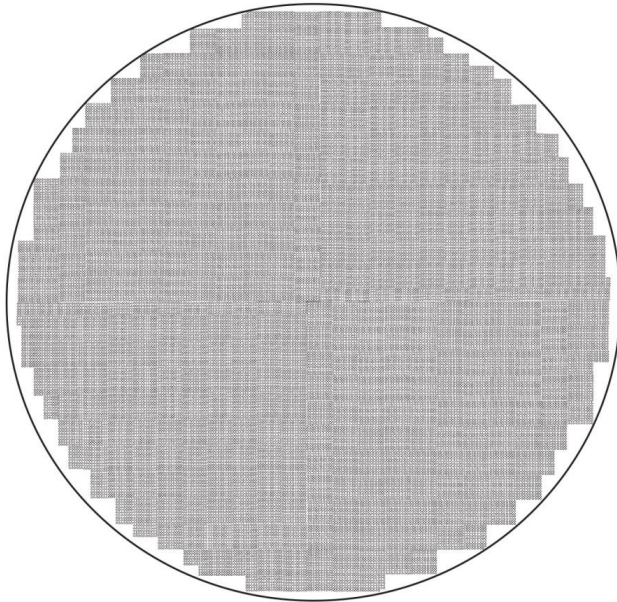
Gordon Harling, President and CEO, CMC Microsystems



# What we are doing



## Silicon interposer – Wafer view



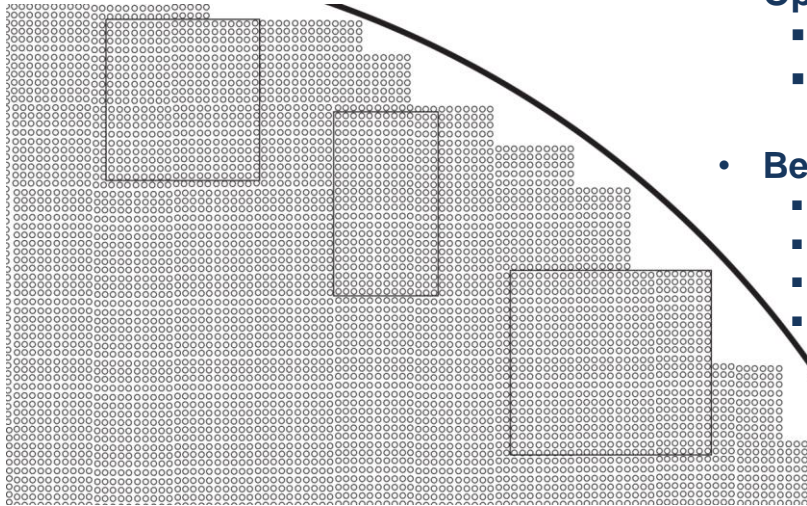
- **Method:**
- We start-off with an 8” wafer
- Pattern (array) TSVs uniformly across whole wafer
- No scribes or free area
- Removes limits to design size
- Standard tiles or custom arrays



# What we are doing



## Silicon interposer – Custom sizes



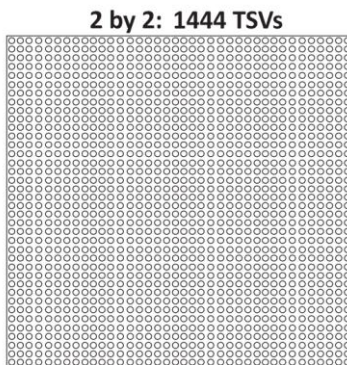
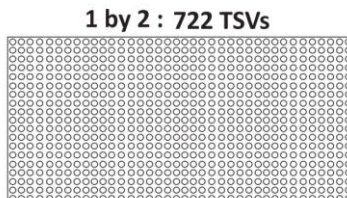
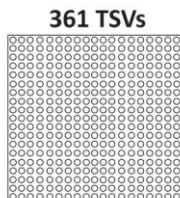
- Options:
  - Custom sizes
  - Quarter wafer / Full Wafer
- Benefits:
  - Larger designs possible
  - Short cycle time
  - TSV wafer inventory
  - Flexibility in size/shape/RDL



# What we are doing for packaging?



## Silicon interposer – Standard Tiles



- Options:
  - Base array 1 cm<sup>2</sup>: 19x19 TSVs
  - 1x2 array: 19x38 TSVs
  - 2x2 array: 38x38 TSVs
- Benefits:
  - Inventoried
  - Reduced cycle time 4-6 weeks for prototyping your design
  - Access to Test Sockets

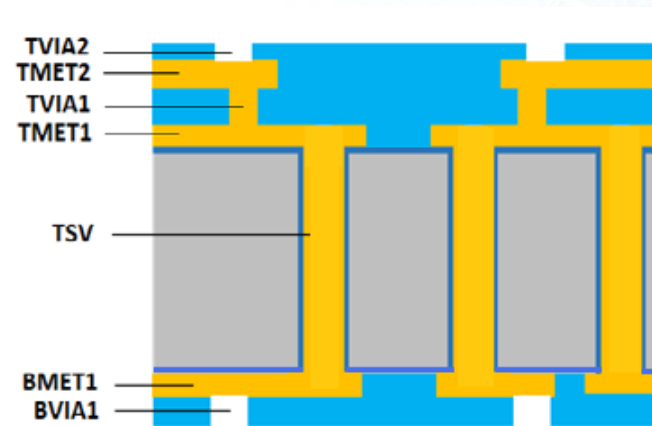


# What we are doing



- Very small sizes:
- 400 $\mu$ m thickness
- 2 top RDL
- 1 bottom RDL
- 5 $\mu$ m metal width / spacing
- TSV diameter: 100 $\mu$ m
- TSV pitch: 500 $\mu$ m
- $\frac{1}{15}$  *Width* *PCB metal*
- $\frac{1}{2}$  *thick* *bare die*

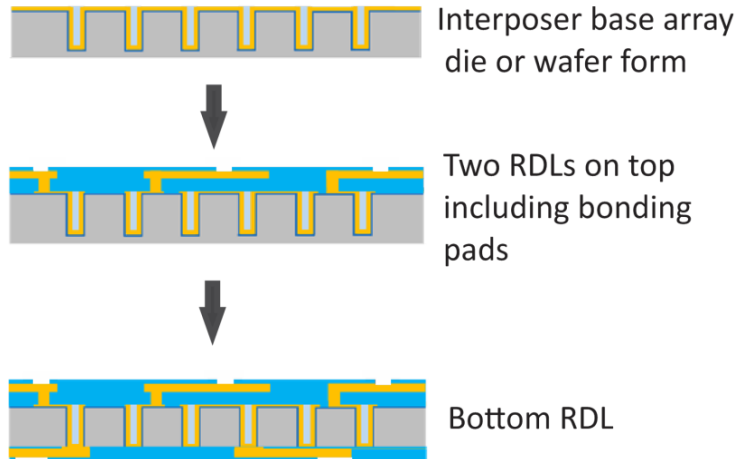
## Silicon interposer – Cross-sectional view



# What we are doing



## Silicon interposer – Flexible manufacturing



### Four process modules:

1. TSV Array formation
2. Top-side patterning
3. Bottom-side patterning
4. Component placement

### Modular approach:

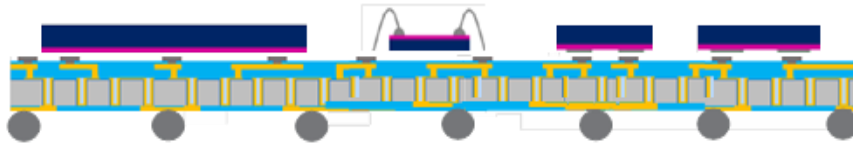
- Wafer hand-off mirrored
- Finished product
- Intercept manufacturing flow outside of validated network



# What we are doing



## Silicon interposer – Component placement



Preferred method Flip-chip → Also:  
Wirebonding

### Process step 4:

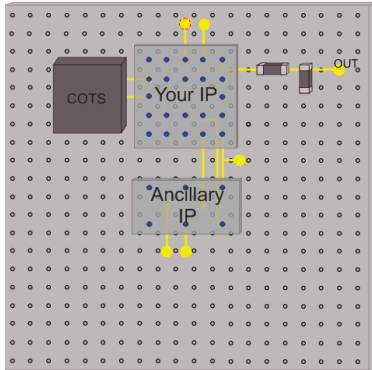
- Ball drop bumping
- Stencil print
- Solder bumping
- Standard BGA:  
100 $\mu$ m diameter 1mm  
pitch
- Underfill



# Why use the interposer

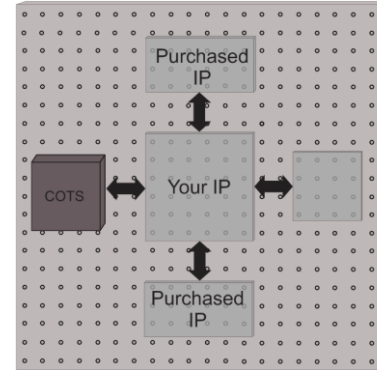


## *FLEXIBLE PROTO – IP Vendors*



- Requirements vs Offer
- Variable demo for customer
- Customer: HW Eval, SW
- Close to final product: Speed, Size, Power

## *RAPID DEMO – SoC Developers*



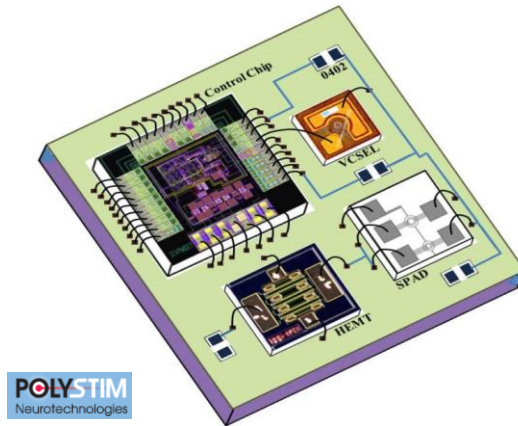
- Close to final IC: Speed, Power, Size
- De-risk of design
- 4-6 weeks turnaround time
- Early software development



# Why use the interposer



## FEASIBILITY – PROOF OF CONCEPT



**On Chip Near InfraRed spectroscopy:  
Portable brain imaging, Optical mammography**

## Benefits:

- Low-cost method
  - Demo
  - PoC
- Sellable form
- Increased capability:  
Speed, Size, Power
- Hiding complexity
- Excellent CTE
- No Outgassing
- Small Size,  
Portability





# Why use the interposer?



	PCB	Interposer
<b>Line width</b>	75 $\mu\text{m}$ (3 mils)	5 $\mu\text{m}$ (0.2 mil)
<b>Line spacing</b>	75 $\mu\text{m}$	5 $\mu\text{m}$
<b>Line thickness</b>	30 $\mu\text{m}$	1 $\mu\text{m}$
<b>Relative Dielectric Const.</b>	4.3	4
<b>Loss tangent</b>	0.025	0.0015
<b>Spacing between layers</b>	165 $\mu\text{m}$	1.5 $\mu\text{m}$
<b>Wiring density</b>	130 lines / cm sq.	600 lines / cm sq.

- Eliminate outgassing for pump down
- Wide temperature range

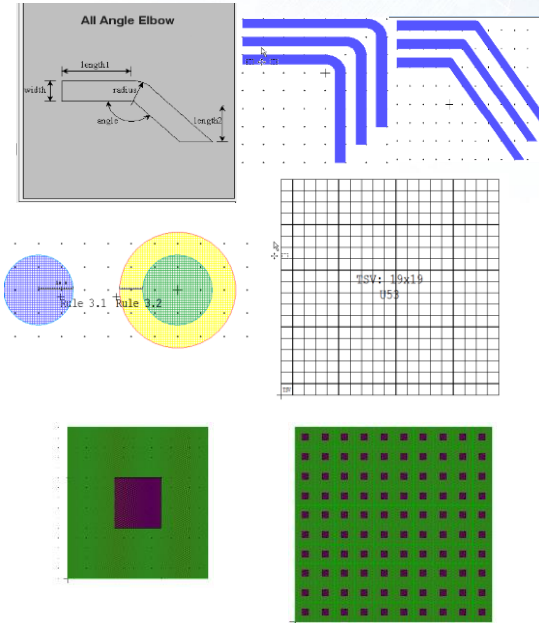


# How we do it



## Process Design Kit (PDK)

- Tanner Tools V2016 currently deployed
  - Curve tools add-on by softMEMS with G-S-G RF trace capability
  - Primitives, Cells for Pads, Contacts, TSV arrays and TSV connections
- Design rules always up to date
- Library of standard components
- Common surface mount and WLCSP footprints

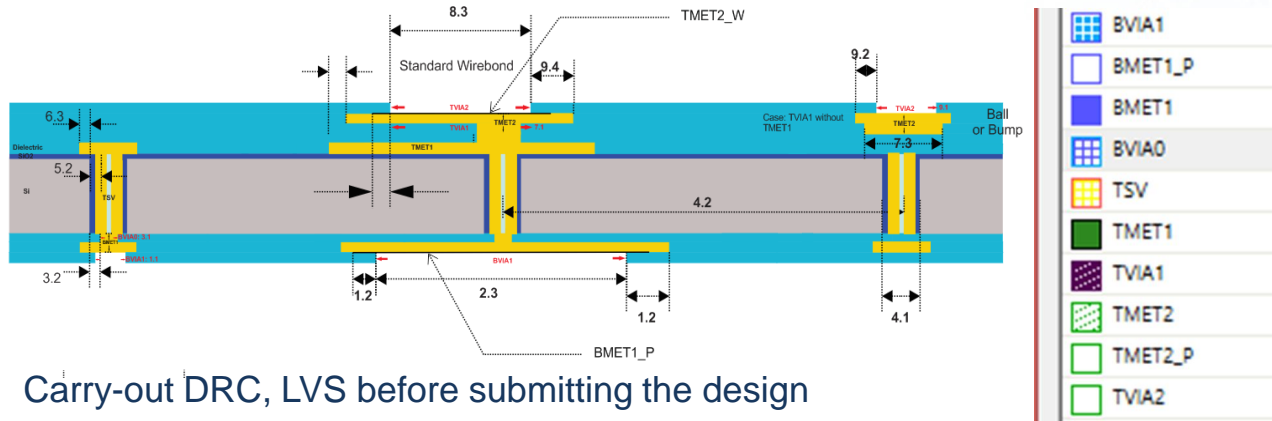


# How we do it



## Process Design Kit (PDK)

- DRC Rules in User's Guide



- Carry-out DRC, LVS before submitting the design
- Migrate your PCB designs

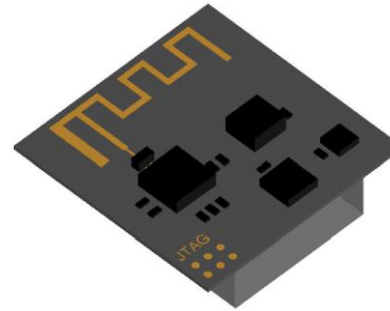
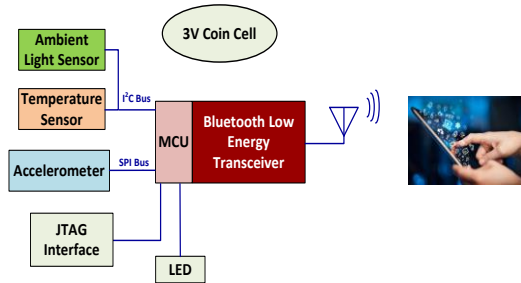


# How we do it



## Reference design 1 – Reusable IP – Crowdsourcing approach

### Compact BLE sensor node



- **Light, temp sensors, accelerometer, CC2640 MCU, coin cell**
- **Antenna incorporated on silicon interposer!**
- **Sharing common blocks of circuitry with users**
- **Library of schematics, layouts**

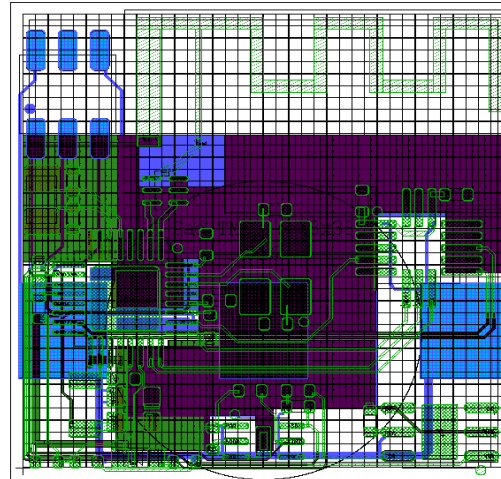
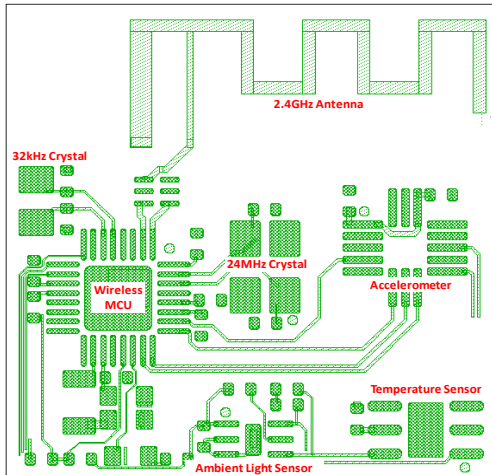


# How we do it



## Reference design 1 – Reusable IP – Crowdsourcing approach

### Compact BLE sensor node



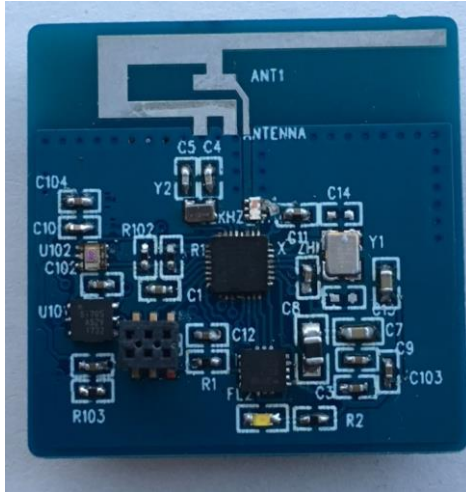
- BVIA1
- BMET1\_P
- BMET1
- BVIA0
- TSV
- TMET1
- TVIA1
- TMET2
- TMET2\_P
- TVIA2



# Current status



## Reference Design 1 – BLE Sensor



- Early PCB Version for FW Eval
- Published FW and Android App in December 2017
- Interposer version with integrated antenna (over TSVs) in design
- CMC plans on making FW available and modifiable for user's needs

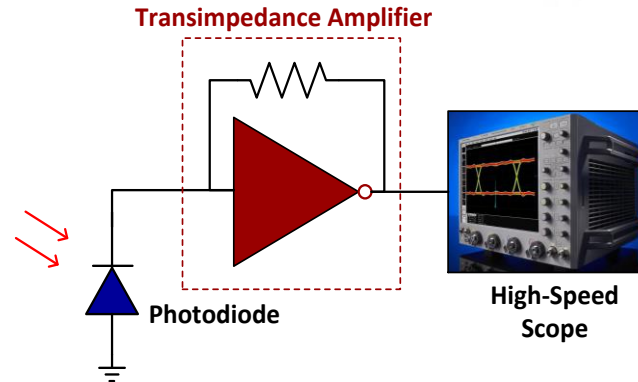
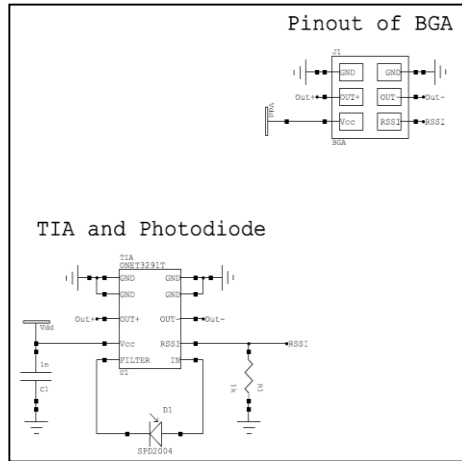


# How we do it



## Reference design 2 – Reusable IP – Crowdsourcing approach

### Optical receiver front-end

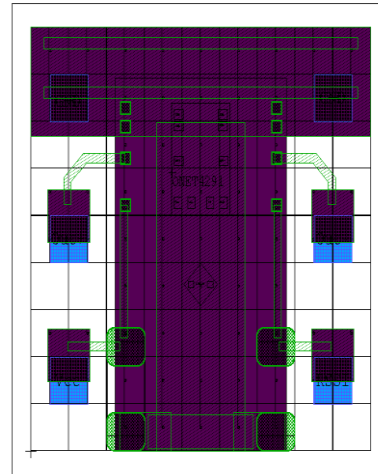
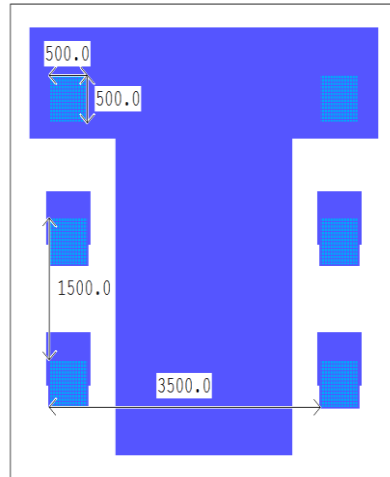


# How we do it



## Reference design 2 – Reusable IP – Crowdsourcing approach

### Optical receiver front-end



- BVIA1
- BMET1\_P
- BMET1
- BVIA0
- TSV
- TMET1
- TVIA1
- TMET2
- TMET2\_P
- TVIA2





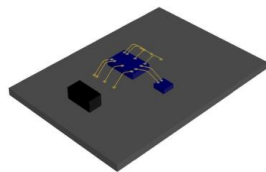
# How we do it



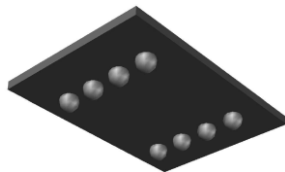
## Reference design 2 – Reusable IP – Crowdsourcing approach

Optical receiver front-end

TOP VIEW



BOTTOM VIEW

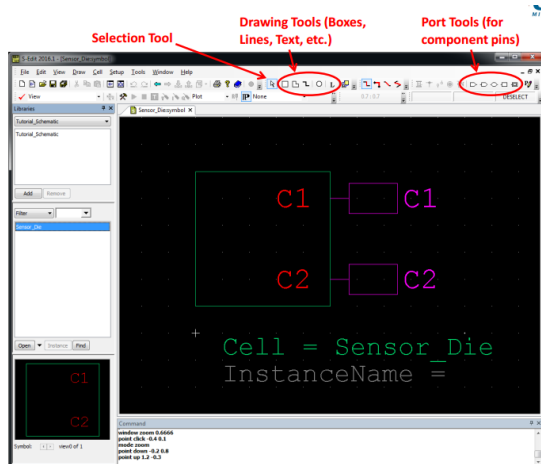


# How we do it



## Tanner Toolkit Features

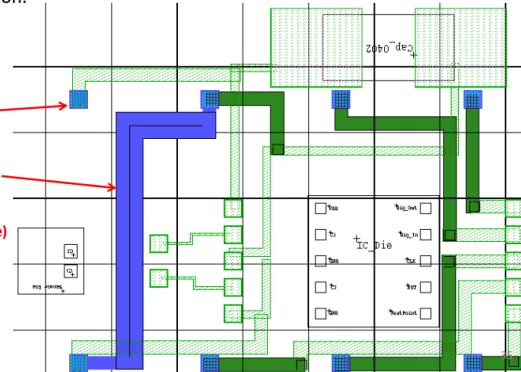
Fully downloadable User's Guides, Training Kits, Rules Decks and Design Tutorials



- In this design, the pitch of BGA bumps is 1mm in the x-direction and 2mm in the y-direction.

Vias going down to the bottom layer with BMET1 pad for BGA bump

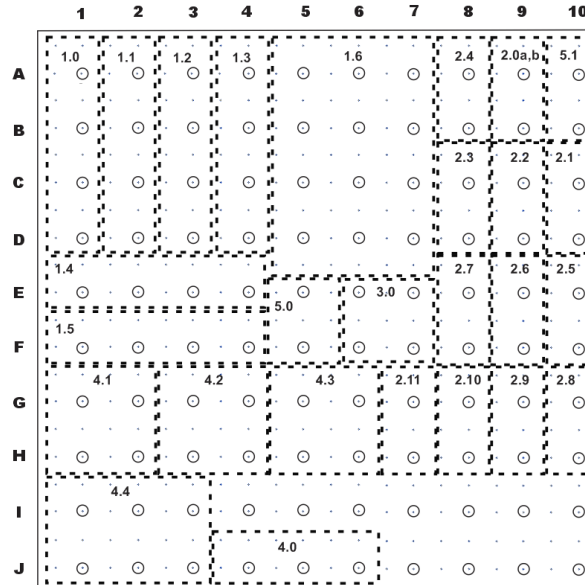
Routing GND on the bottom metal (Can also use a low-resistance ground plane)



# How we do it



## Test Chip – Process Control Module (PCM)



### Tests:

4-point  
resistance,

Contact  
chain,

Max current,

Continuity  
and Isolation,

S-Params on  
G-S-G

### Test chip:

- Each supplier fabricates a PCM
- Choosing supplier according to test chip results

### Suppliers:

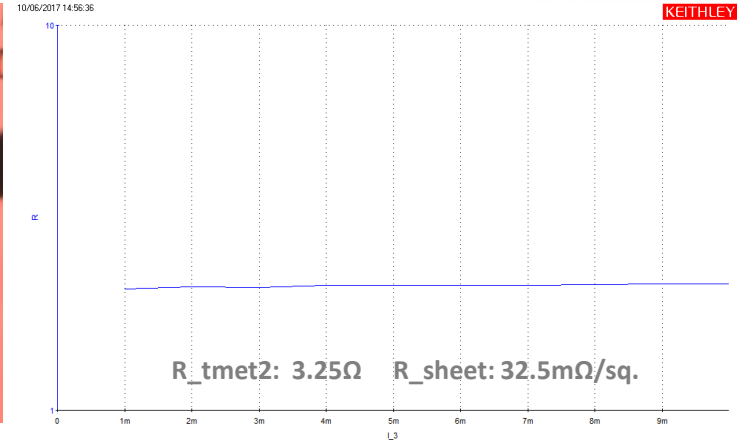
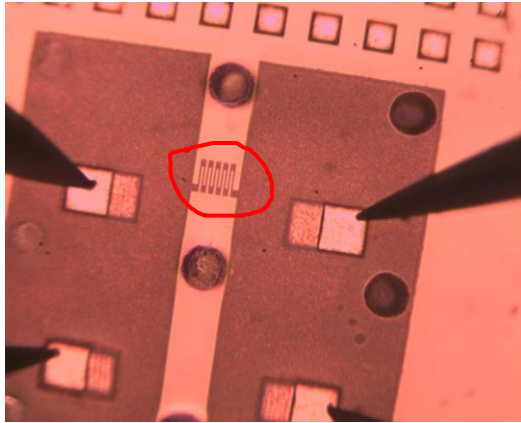
- Design interception
- Skill sets, Equipment, Nature of design



# How we do it



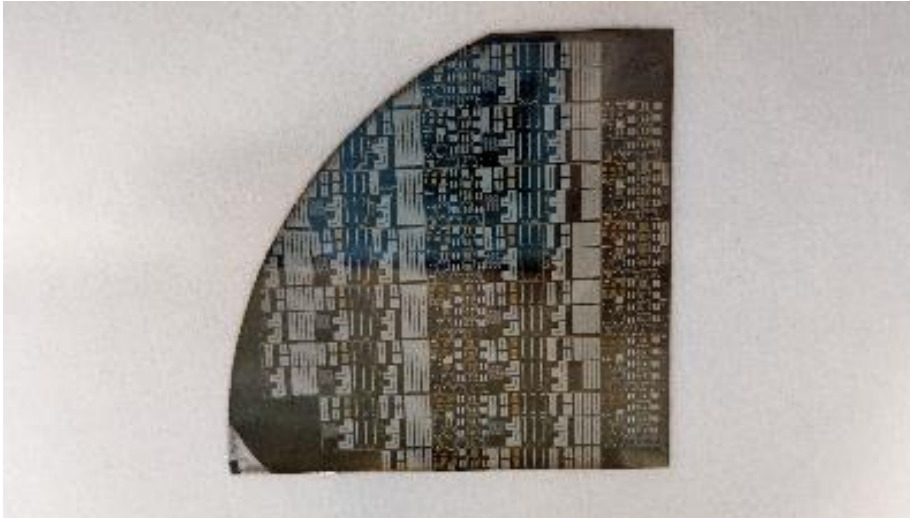
## PCM – 4pt resistance



Follows: TMET1, BMET1, Contact chain, Max current, C&I



# Current status



- **PDK and tools ready**
- **New TSV process in development**
- **First runs of PCMs in 2020 for characterization**

# Community feedback

- What would help advance your technology R&D?
- What are your requirements for integration and packaging?
- Engage with CMC to develop platform technology.
- Other Q&A

- **Contact:**

- [andrew.fung@cmc.ca](mailto:andrew.fung@cmc.ca)      [fab@cmc.ca](mailto:fab@cmc.ca)

# Coming up: NANOverner in Edmonton



**CMC**  
MICROSYSTEMS

**NANOCanada**

**NANOverner: Innovative Materials & Technology**  
November 4 – 6, 2019 | 3 Days, 3 Events! Edmonton, AB

**Lab2Fab Workshop 2019: Innovation for Life**  
November 4, 2019  
NRC Nanotechnology Research Centre  
Edmonton, AB

**Advanced Materials and Nanotechnologies for Health**  
November 5, 2019  
Matrix Hotel  
Edmonton, AB

**Training: Microfabrication Process Engineering using XperiDesk**  
November 6, 2019  
University of Alberta  
Edmonton, AB

[www.cmc.ca/nanoverner-2019](http://www.cmc.ca/nanoverner-2019)

